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of the isolation trench tenches 62 lie below the level of the source and drain implants.

<u>REMARKS</u>

In the advisory action mailed on April 16, 2003, the Examiner has stated "throughout the prosecution, this Examiner has repeatedly urged the applicant to direct to any portion of the originally filed specification regarding a single trench." Applicant responded in its response filed on June 6, 2002, with a statement that this was an annular trench, and in its response filed on March 26, 2003, with an affidavit testifying to the fact that anyone of ordinary skill in the art would *know* that this was a single isolation trench. Applicant is responding again with another affidavit testifying to the fact that in order to be an isolation trench, the *trench must completely surround the device and therefore, the trench can only be a single isolation trench*. In other words, without a trench completely surrounding the device, there would be no isolation.

As stated above, Applicant is submitting another declaration clearly stating that an isolation trench, by definition, must completely surround the device that it is isolating. In addition, Applicant is amending the specification to more clearly describe the claimed invention. No new matter has been added.

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If the Examiner has any questions regarding this response or the Application in general, the Examiner is invited to telephone the undersigned at 775-586-9500.

On the basis of the above remarks, early consideration of this application and early allowance are respectfully requested.

Dated:

Sierra Patent Group, Ltd. PO Box 6149 Stateline, NV 89449 (775) 586-9500

Respectfully submitted, Siefra Parent Group, Ltd.

Reg. No. 47,208